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Ohmic contact-free mobility measurement in ultra-wide bandgap AlGaN/AlGaN devices

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Abstract—We measure the electron density dependence of carrier mobility in ultra-wide bandgap Al$_{0.85}$Ga$_{0.15}$N/Al$_{0.7}$Ga$_{0.3}$N heterostructures, using only Au/Pt Schottky contact deposition and without the need for Ohmic contacts. With this technique, we measure mobility over a 2DEG density range from $10^{10}$ to $10^{14}$ cm$^{-2}$ at an AlGaN/AlGaN heterojunction. At room temperature subthreshold mobility was 4 cm$^2$/Vs and peak mobility 155 cm$^2$/Vs. Peak mobility decreased with temperature as T$^{-0.86}$, suggesting alloy scattering as the dominating scattering mechanism.

Index Terms—AlGaN, mobility, Ohmic contact, Schottky.

I. INTRODUCTION

ULTRA-wide bandgap (UWB) heterojunctions enable higher breakdown voltage capability than the more common AlGaN/GaN field effect transistor devices [1], however, mobility may be a performance limiting factor due to alloy scattering in a ternary channel. Established methods to determine the channel sheet charge density dependence of mobility in devices include field effect mobility and Hall mobility [2]. Such techniques are often limited to measuring mobility in the unbiased case, i.e. at one carrier density, or over a narrow range of carrier density. Gated Hall techniques have been used to measure mobility in AlGaN/GaN structures over almost a decade span of carrier density, e.g. Manfra measured mobility from $2 \times 10^{11}$ to $2 \times 10^{12}$ cm$^{-2}$ [3], where it was found that $\mu \propto n_{2DEG}$, due to scattering from charged dislocations limiting mobility [4]. The gated Hall measurement required insulated gate Hall bars to be fabricated, and a magnetic field applied. In contrast, gate admittance techniques [5] provide mobility data over a much wider carrier density range, using simpler test structures and equipment.

Ohmic contact formation in ultra-wide bandgap semiconductors remains difficult, making FET based mobility measurements challenging. In this work, we demonstrate a technique for measuring mobility without the need for Ohmic contact formation. The technique is suitable for use in characterising mobility in semiconductor materials, and requires only Schottky metal deposition. Using this technique we extract the 2DEG mobility of an UWB device from the weak inversion regime through to the strong inversion unbiased case for the first time. We show that mobility temperature dependence measurements and 2DEG density dependence measurements indicate alloy scattering is the dominant mechanism.

II. EXPERIMENTAL DETAILS

The device structure studied consisted of a barrier layer of 40 nm Al$_{0.85}$Ga$_{0.15}$N:Si$\approx 10^{18}$ cm$^{-3}$, grown on a 550 nm thick UID Al$_{0.7}$Ga$_{0.3}$N buffer that was regrown on an AlN/sapphire template. Schottky barrier electrical contacts of 10 nm Pt covered by 100 nm Au were deposited by e-beam evaporation on top of the barrier in the form of a disc (radius 840 $\mu$m), and surrounding annulus (inner radius 1240 $\mu$m, outer radius 1760 $\mu$m), as shown in Figure 1. The structure forms back-to-back Schottky diodes where the annulus is operating in forward bias and the centre disc in reverse bias.

An Agilent E4980A Precision LCR Meter was used to measure the parallel capacitance and conductance of the disc-annulus test structure, with the annulus as the ground reference side and the oscillating bias applied to the disc contact. To mitigate against the effects of electrical parasitic elements, including stray capacitances, a four point Kelvin measurement was used whereby the disc and annulus Schottky contacts were simultaneously contacted with two probes each. Open and short calibrations of the measurement system were performed including the four point probes in place. This approach removed the effect of cabling and probes from our data, enabling...
accurate $C_V$-G measurement over the wide frequency range used. Admittance-frequency curves were measured from 20 Hz up to 2 MHz at each disc voltage ($V_{disc}$), with an oscillation magnitude of 20 mV. $V_{disc}$ was varied from 0 V to -8 V. The measured threshold voltage for the disc-annulus structure was approximately -7 V. We assume that the true threshold voltage for the heterostructure is within a few hundred mV of that value, once the small voltage drop across the forward biased annulus Schottky diode is subtracted. The full admittance-frequency-voltage (Y-f-V) measurement was repeated at wafer chuck temperatures from 25 °C to 75 °C.

Mobility was extracted from the Y-f-V measurements using an equivalent circuit model, as shown in Figure 1. This method uses the lateral resistance and charge density of the 2DEG to extract mobility and is especially sensitive to the device threshold and sub-threshold regions. The method used here differs from that reported in [5] by the addition of a series capacitance term to represent the annulus Schottky contact ($C_{annulus}$), a resistance to represent the ungated channel ($R_{access}$), and modification to the admittance of each element to account for the circular geometry of the test structure. Based on the demonstration in that paper and in [6] that there was an insignificant GaN/AlGaN heterojunction interface state density, it is assumed here that there are no interface states at the AlGaN/AlGaN heterojunction. There are likely to be bulk traps in the AlGaN barrier, which may add a background contribution to the admittance under reverse bias, however we expect their distorting effect on $G/\omega$-f peak positions, discussed below, to be minimal.

$C_{annulus}$ was calculated from the unbiased 20 Hz disc-annulus capacitance measurement as a series combination using the areas of the two contacts: $C_{annulus} = C_{measured} \times A_{annulus} \times \left( \frac{1}{A_{disc}} + \frac{1}{A_{annulus}} \right)$. The total impedance was then $Z_{total} = Z_{annulus} + Z_{access} + Z_{disc}$. $Z_{annulus}$ is purely capacitive and assumed to be constant over the measurement voltage and frequency range (i.e. a high density 2DEG is always present under the annulus), and $Z_{access}$ is purely resistive. $Z_{disc}$ was constructed iteratively from parallel capacitance elements ($C_{b,i}$ and $C_{x,i}$ in series) and series resistances ($R_i$), as shown. The capacitance of each element of the Schottky disc region is comprised of three capacitances in series as outlined in [7]: (i) the barrier itself; (ii) an additional thickness (set at 1 nm) due to the separation of the 2DEG from the AlGaN/AlGaN interface; (iii) the capacitance from the 2DEG density which is limited by the finite electronic density of states, calculated using $A_i \times q \times n_{2DEG}/2kT$, where $A_i$ is the area of the $i^{th}$ element. This final term is due to the change in charge in the 2DEG as the applied voltage shifts the Fermi level [8]. The factor of 2 in (iii) was applied for the strong inversion region, changing to 1 in weak inversion where the 2DEG density is insufficient to screen the electric field [9]. The electrical permittivity of Al$_{0.85}$Ga$_{0.15}$N was determined following [10]. The resistance of each element is given by $R_{sheet} = \frac{R_2}{2\pi \ln \frac{R_2}{R_1}}$, where $R_2$ and $R_1$ are the outer and inner radii of each element. $R_{access}$ was found similarly. $R_{sheet}$ was taken to be $\frac{1}{\mu Q}$, where Q is the areal carrier density ($n_{2DEG}$), and $\mu$ is the channel mobility. $Q$ was determined by integrating the $C_{disc}$ - $V$ curve formed from the 20 Hz capacitance measurement taken at each $V_{disc}$ value, after subtracting the capacitance of the annulus. Therefore $\mu$ is the only free parameter in the fit.

The admittance of the model structure is given by $Y = \frac{Z_{total}}{\omega}$. The real component of the admittance is the conductance, which when plotted as $G/\omega$ against $\omega$ displays a characteristic peak for each $V_{disc}$ tested [11], as shown in Figure 2. The fitting algorithm used the logarithm of the ratio of the peak positions for the measured and model curves as the optimisation target to be minimised. To determine the frequency of each peak an appropriately weighted Gaussian function was fitted to the curves and the position of its centre was taken as the peak in the $G/\omega$-frequency curve. A Gaussian function was chosen for computational efficiency in fitting the peak region of the model and data; it does not form part of our physical impedance model. $\mu$ was then adjusted to reduce the difference between the peak positions of the two curves, a new $Z_{total}$ calculated, and the iteration repeated until the required tolerance was reached and $\mu$ had been found for the $V_{disc}$ value. This procedure was repeated at each $V_{disc}$ value, and at each temperature.

III. RESULTS AND DISCUSSION

Taking the data in Figure 2 a peak mobility value of 155 cm$^2$/Vs at 25 °C, at $n_{2DEG} = 5.1 \times 10^{12}$ cm$^{-2}$ corresponding to a voltage drop of -2.95 V across the barrier was determined for this structure. Hall mobility measurements using large area indium contacts corresponding to the unbiased case on the same wafer determined values of 135 cm$^2$/Vs at 9.9 $\times$ 10$^{12}$ cm$^{-2}$; contactless sheet resistance using a Lehighton instrument and Hg-probe C-V measurements, again for the unbiased case, found 180 cm$^2$/Vs at 9.8 $\times$ 10$^{12}$ cm$^{-2}$. For comparison our method measured a mobility of 122 cm$^2$/Vs at 9.51 $\times$ 10$^{12}$ cm$^{-2}$ for the unbiased case. The numbers are broadly in agreement; small differences may have arisen due to barrier thickness variations between the different wafer locations that each sample was taken from and the impact of any voltage drop across the annulus.
Figure 4. The inset shows that peak mobility decreases as T−0.86 over the temperature range tested. This temperature dependence is significantly reduced from what is expected for optical phonon scattering (T−1.5) [14], and is closer to the T−0.5 expected for alloy scattering [15]. A T−0.7 to T−0.85 dependence of alloy disorder scattering on temperature was found by Glicksman in Germanium-Silicon alloys [16] after removal of ionised defect and phonon mobility limits. The peak mobility temperature dependence is therefore further evidence in favour of alloy scattering being the mobility limiting factor in these Al0.85Ga0.15N / Al0.7Ga0.3N devices.

Over the 25 °C to 75 °C temperature range tested Schottky contact leakage did not adversely affect our measurements. Leakage current would increase as chuck temperature is increased, however as demonstrated in [11], its influence is easily distinguished as an increase in \( \frac{Q}{\omega} \) as measurement frequency is decreased. We expect that our technique should be suitable for use at higher operating temperatures, a regime where UWB heterojunction devices are of particular interest.

IV. CONCLUSIONS

It was shown that 2DEG mobility can be measured from weak inversion through to the unbiased case, in ultra-wide bandgap semiconductor AlGaN heterostructures, via a Y-f-V technique using only Schottky contacts. This technique may therefore be especially valuable for early feedback on new material developments. The maximum mobility values extracted using this technique are in good agreement with those measured by Hall measurement. Concentration-dependent mobility and temperature-dependent mobility at around 5 \( \times \) 10^{12} cm\(^{-2}\) suggest that alloy scattering is presently limiting peak mobility in this material. Reducing interface roughness may however increase mobility to closer to 177 cm\(^2\)/Vs.

REFERENCES


